

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application No. : **10/040,042**
Applicant : **Wei-Yu Su**
Filed : **November 7, 2001**
TC/A.U. : **1746**
Confirmation No. : **1835**
Title : **Method for Reduction of Photomask Defects**
Examiner : **El Arni, Zeinab**
Attorney Docket No : **N1085-90003**
Customer No. : **08933**

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

AMENDMENT AND RESPONSE

In response to the Office Action of April 27, 2006, please amend the above-identified application as follows:

Amendments to the Claims are reflected in the listing of claims which begins on page 2 of this paper.

Remarks begin on page 6 of this paper.